

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S2	7920	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:04
S3	97	((dry cleaning) or dry\$cleaning) same reactor	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 10:42
S4	9	S2 and S3	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 10:29
S5	1	("5861066").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/25 10:32
S6	1	("6884297").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/25 10:32
S7	15	("20020023588" "20030041971" "20030221780" "20040149212" "20040187780" "5935338" "6117244" "6120605" "6183563" "6364954" "6402848" "6582522" "6586343" "6656838" "6802906").PN. OR ("6884297").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/25 10:41
S9	1	("6312526").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/25 10:41
S12	21	((dry clean\$3) or dry\$clean\$3) same reactor same dummy	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 10:43
S13	3	S2 and S12	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:33
S14	4	S2 and ((dummy with (wafer or semi\$1conductor)) same (rf or radio frequency))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:46
S15	451	S2 and ((wafer or semi\$1conductor) same (rf or radio frequency))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:40

EAST Search History

S17	140	S2 and ((wafer or semi\$1conductor) same (rf or radio frequency) same etch\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:40
S18	8	S2 same (wafer or semi\$1conductor) same (rf or radio frequency) same etch	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:43
S19	11	S2 same (wafer or semi\$1conductor) same (rf or radio frequency) same etch\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 11:43
S20	7920	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 13:48
S21	0	S20 same (bcl with (ar or argon))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 13:51
S28	49	S20 and ("bcl.sub.3" with (ar or argon))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 13:54
S34	6	S20 and ((dummy (wafer or semi\$1conductor)) with clean\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 15:09
S35	1	("20040014327").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/02 11:21
S36	3	S20 and ((clean with reactor) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 18:00
S37	1081	bcl\$ with (ar or argon)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/25 18:01
S39	17	S20 and ((bcl\$ with (ar or argon)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 11:43
S40	8	gas curtain hole	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 08:58

EAST Search History

S41	61	(rf or (radio frequency)) with clean\$3 with activat\$3 with gas	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 08:59
S42	7920	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 08:59
S43	10	S41 and S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 08:59
S45	75	S42 and ((clean\$3 with (reactor or chamber)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:21
S46	11	S42 and ((clean\$3 with (reactor or chamber)) same (rf or (radio frequency))) same (shower\$1head or (shower head)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:33
S47	2	S42 and ((clean\$3 with (reactor or chamber)) same ((rf or (radio frequency)) with ((shower\$1head or shower) or (distribution or dispersion)) with head))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:38
S48	438	(rf or (radio frequency)) with (shower\$1head or shower or distribution or dispersion) with head	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:39
S49	13	((rf or (radio frequency)) with (shower\$1head or shower or distribution or dispersion) with head) same clean	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 10:47
S50	1	("5449410").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/26 10:47
S51	7	("4960488" "5158644" "6030902").PN. OR ("6305390").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/27 14:41
S52	11	(semiconductor or wafer) same ((shower\$1head or (shower head)) with first with spray with hole)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 12:12
S54	71	clean\$3.ti. and (reactor.ti. or chamber.ti.) and plasma.ti. and (semiconductor or wafer)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 12:16
S55	12	clean\$3.ti. and (reactor.ti. or chamber.ti.) and plasma.ti. and (semiconductor or wafer) and (shower\$1head or (shower head))	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 12:19

EAST Search History

S56	2	clean\$3.ti. and (reactor.ti. or chamber.ti.) and plasma.ti. and (semiconductor or wafer) and ((shower\$1head or (shower head)) with first)	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 12:19
S58	75	((dummy with (wafer or semi\$1conductor)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:48
S61	4	(dummy with (wafer or semi\$1conductor)) same (rf or (radio frequency)) same (shower\$1head or (shower head))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:49
S62	9	(dummy with (wafer or semi\$1conductor)) same (rf or (radio frequency)) same (shower\$1head or shower or dispersion or distribution)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:55
S63	951	(wafer or semi\$1conductor) same (rf or (radio frequency)) same (shower\$1head or shower)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 12:55
S64	15	(wafer or semi\$1conductor) same (rf or (radio frequency)) same (shower\$1head or shower) same ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 13:22
S65	86	(first with ((source or reaction) gas) with (hole or inject\$3)) same (wafer or semiconductor) same (reactor or chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 14:00
S66	1	("6,921,437").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/26 14:00
S67	19	("20020092471" "20040050325" "20040050326" "20040099377" "20040221809" "5010842" "5422139" "5453124" "5567267" "5595606" "5622606" "5766364" "5792261" "5938333" "6086677" "6302964" "6333019" "6499425" "6502530").PN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/26 14:17
S68	1	("6,086,677").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/26 14:59
S78	2	((rf or (radio frequency)) with power with etch\$3 with rate with (increas\$3 or greater)) same bcl\$	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:20

EAST Search History

S79	4	((rf or (radio frequency)) with etch\$3 with rate with (increas\$3 or greater)) same bcl\$	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:21
S80	19416	(rf or (radio frequency)) with (chuck or block or susceptor)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:41
S81	26	((rf or (radio frequency)) with (chuck or block or susceptor)) same S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:43
S82	385	((rf or (radio frequency)) with (chuck or block or susceptor)) same clean\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:43
S83	130	((rf or (radio frequency)) with (chuck or block or susceptor)) with clean\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:49
S84	2406	dummy near wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:50
S85	311	S84 with (chuck or block or susceptor)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 15:50
S87	2	(S84 with (chuck or block or susceptor)) same (rf or (radio frequency)) same S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 16:02
S88	37	(chuck or block or susceptor) same (rf or (radio frequency)) same S42	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 16:03
S90	10	bcl\$ same ((test\$3 or sacrific\$6 or blank or dummy) near wafer) same (rf or (radio frequency)) same (ar or argon)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/26 16:18
S91	7941	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 08:55

EAST Search History

S96	174	dummy near wafer.clm.	US-PGPUB; USPAT; USOCR; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 09:02
S97	21	S91 same dummy	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 08:55
S98	13	S91 and (dummy near wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 09:47
S99	29	(in situ) near plasma near clean\$3	US-PGPUB; USPAT; USOCR; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:27
S100	1	("6,387,185").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/27 09:04
S101	1	("5728602").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/04/27 09:47
S102	85	(in situ) with plasma with clean\$3	US-PGPUB; USPAT; USOCR; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 13:10
S103	13	("5728602").URPN.	USPAT	ADJ	ON	2006/04/27 10:51
S104	1240	dummy substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:52
S105	4	S104 and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:54
S106	226	bcl\$ and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:55

EAST Search History

S10 7	3	bcl\$ and S91 and dummy	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 10:57
S10 8	2	bcl\$ and S91 and ((sacrific\$6 or test or blank) near (wafer or substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 11:04
S10 9	2058	activat\$3 with clean\$3 with gas	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 11:04
S11 0	28	S109 and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2006/04/27 11:04
S11 1	8	clean same ((bcl\$ with (ar or argon)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 15:58
S11 2	6	S91 and ((NF\$6 with (ar or argon)) same (rf or (radio frequency)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 11:48
S11 5	1895	curtain near gas	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 12:41
S11 6	61	S91 and S115	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 13:07
S12 4	24	((deposit\$3 with chamber) same (rf or (radio frequency)) same clean) and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 13:48
S12 6	109	plasma with etch\$6 with dummy (substrate or wafer) with clean\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 14:42
S12 7	84	S126 and cvd	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 15:28

EAST Search History

S13 2	83	((protect\$6 or prevent\$6) with (dummy wafer) with (block or wafer or substrate or chuck or susceptor) with clean\$6 with (plasma or rf or (radio frequency))) and cvd and (heat\$6 with (block or chuck or susceptor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 15:39
S13 4	3	(clean\$6 same S91 same (rf or (radio frequency))) and (heat\$6 with (block or chuck or susceptor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:01
S13 5	35	(clean\$6 same (rf or (radio frequency))) and (heat\$6 with (block or chuck or susceptor)) and S91	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:10
S13 6	197	(shower\$1head or (shower head)) with first with second with hole	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:10
S13 7	92	((shower\$1head or (shower head)) with first with second with hole) and (ald or cvd)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:11
S13 8	85	((shower\$1head or (shower head)) with first with second with hole) and (ald or cvd) and (heat\$6 with (substrate or wafer or chuck or block or susceptor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:44
S14 1	2	((sacrific\$6 or test or blank) (wafer or substrate)) same S91	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:46
S14 2	3	((dummy wafer) with (plasma or rf or (radio frequency)) with clean) and (heat\$6 with (block or chuck or susceptor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/27 16:50
S14 6	95	(((dummy wafer) with (plasma or rf or (radio frequency)) with clean\$6) and (heat\$6 with (block or chuck or susceptor)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:08
S14 7	7941	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:08
S14 8	3	(((dummy wafer) with (plasma or rf or (radio frequency)) with clean\$6) and (heat\$6 with (block or chuck or susceptor))) and S147	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:12

EAST Search History

S14 9	0	(((test or blank or sacrific\$6) near (substrate or wafer)) with (plasma or rf or (radio frequency)) with clean\$6) and (heat\$6 with (block or chuck or susceptor))) and S147	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:13
S15 0	2	(((test or blank or sacrific\$6 or dummy) near (substrate or wafer)) with (plasma or rf or (radio frequency)) with clean\$6) and (heat\$6 with (block or chuck or susceptor))) and ((curtain or (deposition control\$6) or confinement) near gas)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:53
S15 1	0	((in\$1situ or (in situ)) with clean\$6) same (rf or (radio frequency)) same ((dummy or blank or test or sacrific\$6) with (wafer or substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:55
S15 2	5	((in\$1situ or (in situ)) with clean\$6) same (rf or (radio frequency) or plasma) same ((dummy or blank or test or sacrific\$6) with (wafer or substrate))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 08:55
S15 3	49	("4924890" "4936329" "5014217").PN. OR ("5314509").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/28 09:06
S15 4	64	134/1.1.ccls. and dummy	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 11:28
S15 5	23	S147 and (first with second with hole with (shower\$1head or (shower head)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 11:38
S15 6	4	("5567243" "5595606").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 11:39
S15 8	87	("4209357" "4625678" "4951603" "5252131").PN. OR ("5595606").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2006/04/28 11:43
S15 9	15	S158 and S147	USPAT	ADJ	ON	2006/04/28 15:42
S16 0	7941	(atomic layer deposition) or ald	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 15:44

EAST Search History

S16 4	69	S160 and (((in\$1situ or (in situ)) with clean\$6) same (rf or (radio frequency) or plasma))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 16:09
S16 6	247	S160 and (((chamber or reactor) with clean\$6) same (rf or (radio frequency) or plasma))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 16:49
S16 7	36	S160 and (((chamber or reactor) with clean\$6) same (ion))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 16:59
S16 8	57	S160 and clean\$6.ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:00
S16 9	18	S160 and clean\$6.ti. and (rf or (radio frequency))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:03
S17 0	114	("20020029747" "20030019428" "20030029566" "20030038127" "20030072639" "20030079686" "20030116087" "20030129106" "20030132319" "20030221780" "20040069225" "20040070346" "20040219789" "20050205110" "20050218507" "20050221552" "20050230350" "4209357" "4579618" "4585920" "4872947" "4886570" "4892753" "4951601" "5000113" "5030319" "5186718" "5198034" "5228501" "5231690" "5238499" "5328558" "5345999" "5451259" "5500249" "5516367" "5800686" "5844195" "5846332" "5855681" "5856240" "5885404" "5951776" "5993916" "6083344" "6086677" "6176198" "6238513" "6350320" "6364949" "6364954" "6446572" "6544340" "6603269" "6638810" "6656831" "6679981" "6740585" "6878206").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:04
S17 1	39	S170 and clean\$6 same (plasma or rf or (radio frequency))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:05
S17 2	8	S170 and (clean\$6 same (plasma or rf or (radio frequency))) and S160	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:16

EAST Search History

S17 3	244	S160 and ((ar or argon or nitrogen or "n.sub.2") with clean\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:16
S17 4	75	S160 and ((ar or argon or nitrogen or "n.sub.2") with clean\$6 with (reactor or chamber))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:21
S17 5	30	S160 and (ar or argon or nitrogen or "n.sub.2") and clean\$6.ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:22
S17 6	20	S160 and ((ar or argon or nitrogen or "n.sub.2") same (plasma or rf or (radio frequency))) and clean\$6.ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/04/28 17:22
S17 7	44	134/1.1.ccls. and (dummy wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 13:20
S17 8	17	134/1.1.ccls. and (ALD or (atomic layer))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 08:36
S17 9	299	134/1.1.ccls. and (CVD or (chemical layer))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 15:07
S18 0	642	clean\$6 with (dummy (wafer or substrate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 15:38
S18 1	4	S180 with (shower\$1head or (shower head))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 15:39
S18 2	18	(ald or (atomic layer)) and (residue with wall with (chamber or reactor))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 16:20

EAST Search History

S18 4	8	(ald or (atomic layer)) same (residue with wall)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 16:22
S18 5	51	(ald or (atomic layer)) and (residue with wall)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/01 16:25
S18 6	80	(ald or (atomic layer)) and clean\$6. ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 08:58
S18 9	16	134/1.1.ccls. and (ALD or (atomic layer)) and clean\$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 08:36
S19 0	32	(ald or (atomic layer)) with deposit\$6 with residue	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 09:01
S19 1	1	("20040014327").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/02 09:01
S19 2	1	("20040180553").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/02 11:57
S19 4	0	(ALD or (atomic layer (deposition or epitaxy))) with (pre\$1coat or (pre coat))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 15:19
S19 6	245	((ALD or (atomic layer (deposition or epitaxy))) with film with deposit\$6) same (("Al.sub.2O.sub.3" or "HfO.sub.2" or "ZrO.sub.2." or alumina) with (deposit\$6 or film or layer))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 12:10
S19 7	200	427/248.1 and ((ALD or (atomic layer (deposition or epitaxy))) with film with deposit\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 12:10
S19 8	16	427/248.1 and (((ALD or (atomic layer (deposition or epitaxy))) with film with deposit\$6) same (("Al.sub. 2O.sub.3" or "HfO.sub.2" or "ZrO. sub.2." or alumina) with (deposit\$6 or film or layer)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 12:22

EAST Search History

S19 9	2	(ALD or (atomic layer (deposition or epitaxy))) same (pre\$1coat or (pre coat))	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 12:23
S20 0	1	("20030165620").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/02 15:13
S20 1	20	("4960488" "5338363" "5522934" "5670218" "5988187" "6183563" "6217658" "6573184" "6579372" "6626185").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 15:19
S20 3	4	(ALD or (atomic layer (deposition or epitaxy))) and ((clean\$6 near gas) same bcl\$)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 15:21
S20 4	75	(ALD or (atomic layer (deposition or epitaxy))) and ((plasma or rf or (radio frequency)) same bcl\$)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/02 15:23
S20 5	24	(ALD or (atomic layer (deposition or epitaxy))) and ((plasma or rf or (radio frequency)) same bcl\$ same clean\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/03 10:57
S20 6	11	(ALD or (atomic layer (deposition or epitaxy))) and ((shower\$1head or (shower head)) with (isolat\$6 or insulat\$6) with electric\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/03 11:26
S20 7	1	("6886491").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/03 11:17
S20 8	1	("20020129769").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/03 11:17
S20 9	147	(cvd or (chemical vapor deposition)) and ((shower\$1head or (shower head)) with (isolat\$6 or insulat\$6) with electric\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2006/05/03 11:28
S21 0	1	("6079356").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/03 11:28
S21 1	1	("20020007790").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/05/09 16:33